

Autosamdri®-931 Multi-Application CPD

3.40" Process Chamber, *Cleanroom Version*



tousimis


- *Multi-Application Critical Point Dryer for Cleanroom Use*
- *"Stasis Software" for Challenging Sample Types*
- *Winner of Microscopy Today Innovation Award*
- *Post Process Data Review*
- *HF Compatible Holders Included with System*
- *Program and Save Custom Recipes*
- *Made in U.S.A.*

Autosamdri®-931 with 3.40in Chamber (Cat. # 8787F)

FEATURES

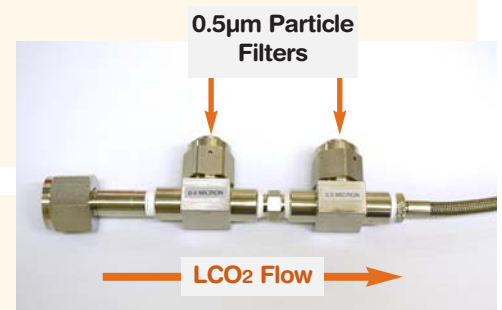
- Cleanroom Material Fabricated Static Free Design
- Bright LCD Touchscreen Control
- Default "Automode" setting suitable for most wafer and die MEMS applications
- Process up to 5 substrates per process run (either Wafers or Die)
- HF Compatible Holders for 3" (75mm), 2" (50mm) diameter wafers and 10mm square die included with system
- Create and save custom Recipes exactly for your specific sample needs
- Easy View Placement of Micro Metering Valves with Vernier Handles
- Slow Fill feature protects the most delicate samples
- Fast adiabatic chamber cooling (\approx 3 minutes from 25°C to 3°C)
- Maintenance Free Non-Mechanical Vortex Swirl™ Purge Stirring
- External 0.5 μ m Post-Purge filter access for easy preventive maintenance
- External LCO₂ tank supply particulate filtration using 'Double T-Filter' design with 99.5%+ retention
- Internal filtration delivers filtered LCO₂ down to 0.08 μ m with 99.999+% retention directly into process chamber
- Internal SOTER™ Condenser quietly separates waste alcohol and CO₂ while eliminating any freeze up or static discharge
- EZ top loading process chamber with LED illumination
- "Stasis Software" for drying GELS and other challenging sample types
- Post Process Previous Run Data Review
- All components meet CE, UL and/or U.S. Military specifications
- 2 year warranty on all parts and labor
- Made in U.S.A.



Released Cantilevers after Thermal Annealing
Nicolas André
Université Catholique de Louvain, Belgium

SPECIFICATIONS

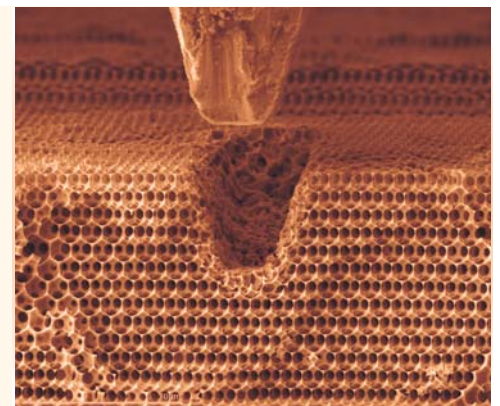
- Cabinet: (W) 15.0" (38.0cm) x (H) 13.25" (33.5cm) x (D) 20" (50.8cm)
- System Set-Up Area Required: (W) 24" (61cm) x (D) 22" (56cm)
- Chamber size:
 3.40" ID x 1.25" Depth (86.36mm ID x 31.75mm Depth) - 186ml Volume
- Pressure Gauge Range: 0 to 2000 psi, Temperature Range - 30°C to 60°C
- 120V or 220V Models Available



Double T-Filter Assembly (#8785)
 Pre-Installed onto High Pressure Hose

STANDARD ACCESSORIES

- Flexible High-Pressure LCO₂ Supply Hose, 10ft (3.0m)
 Note: Other lengths available upon request up to 50ft (15m)
- HF Compatible Substrate Holders included: 3" (75mm) and 2" (50mm) wafer holders as well as a 10mm square die holder for up to 5 die
- Chamber Insert included that reduces LCO₂ consumption and reduces chamber ID from 3.40" down to 1.25"
- Double T-Filter Assembly (#8785-see insert picture) pre-installed onto the LCO₂ high-pressure hose. LCO₂ filtered twice thru 0.5 μ m filters prior to LCO₂ entering Autosamdri®-931 process chamber
- Static Free Exhaust Tubing
- Flow Meter supplied allows precise BLEED Exhaust Calibration
- Spare chamber O-rings (2), LED chamber lamp (1), and 5A slo-blow fuses (2)
- User Manual and Check-Out Data Sheet
- Installation Tool Kit
- **Free Lifetime Technical Support**



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Autosamdri®-931 Multi-Application CPD

2.50" Process Chamber, *Cleanroom Version*



tousimis


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- *Post Process Data Review*
- *HF Compatible Holders Included with System*
- *Program and Save Custom Recipes*
- *Made in U.S.A.*

Autosamdri®-931 with 2.50in Chamber (Cat. # 8787E)

FEATURES

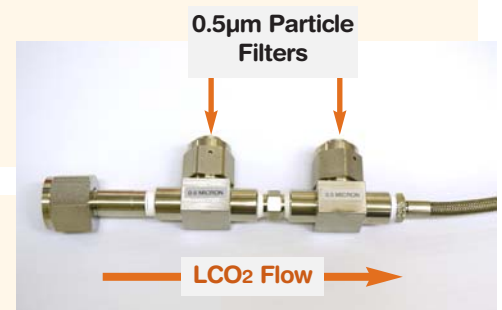
- Cleanroom Material Fabricated Static Free Design
- Bright LCD Touchscreen Control
- Default "Automode" setting suitable for most wafer and die MEMS applications
- Process up to 5 substrates per process run (either Wafers or Die)
- HF Compatible Holders for 2" (50mm) diameter wafers and 10mm square die included with system
- Create and save custom Recipes exactly for your specific sample needs
- Easy View Placement of Micro Metering Valves with Vernier Handles
- Slow Fill feature protects the most delicate samples
- Fast adiabatic chamber cooling (\approx 2 minutes from 25°C to 3°C)
- Maintenance Free Non-Mechanical Vortex Swirl™ Purge Stirring
- External 0.5 μ m Post-Purge filter access for easy preventive maintenance
- External LCO₂ tank supply particulate filtration using 'Double T-Filter' design with 99.5%+ retention
- Internal filtration delivers filtered LCO₂ down to 0.08 μ m with 99.999+% retention directly into process chamber
- Internal SOTER™ Condenser quietly separates waste alcohol and CO₂ while eliminating any freeze up or static discharge
- EZ top loading process chamber with LED illumination
- "Stasis Software" for drying GELS and other challenging sample types
- Post Process Previous Run Data Review
- All components meet CE, UL and/or U.S. Military specifications
- 2 year warranty on all parts and labor
- Made in U.S.A.



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SPECIFICATIONS

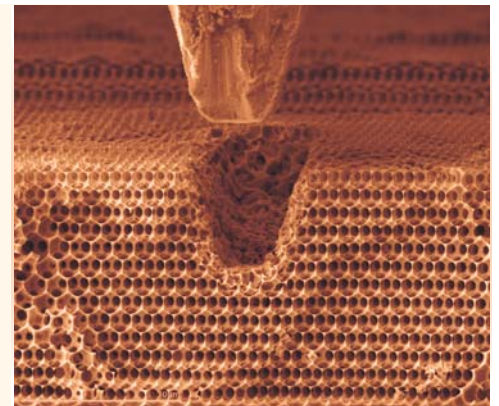
- Cabinet: (W) 15.0" (38.0cm) x (H) 13.25" (33.5cm) x (D) 20" (50.8cm)
- System Set-Up Area Required: (W) 24" (61cm) x (D) 22" (56cm)
- Chamber size:
 2.50" ID x 1.25" Depth (63.50mm ID x 31.75mm Depth) - 100ml Volume
- Pressure Gauge Range: 0 to 2000 psi, Temperature Range - 30°C to 60°C
- 120V or 220V Models Available



Double T-Filter Assembly (#8785)
 Pre-Installed onto High Pressure Hose

STANDARD ACCESSORIES

- Flexible High-Pressure LCO₂ Supply Hose, 10ft (3.0m)
 Note: Other lengths available upon request up to 50ft (15m)
- HF Compatible Substrate Holders included: 2" (50mm) wafer holder as well as a 10mm square die holder for up to 5 die
- Chamber Insert included that reduces LCO₂ consumption and reduces chamber ID from 2.50" down to 1.25"
- Double T-Filter Assembly (#8785-see insert picture) pre-installed onto the LCO₂ high-pressure hose. LCO₂ filtered twice thru 0.5 μ m filters prior to LCO₂ entering Autosamdri®-931 process chamber
- Static Free Exhaust Tubing
- Flow Meter supplied allows precise BLEED Exhaust Calibration
- Spare chamber O-rings (2), LED chamber lamp (1), and 5A slo-blow fuses (2)
- User Manual and Check-Out Data Sheet
- Installation Tool Kit
- **Free Lifetime Technical Support**



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Autosamdri®-931 Multi-Application CPD

1.25" Process Chamber, *Cleanroom Version*



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Autosamdri®-931 with 1.25in Chamber (Cat. # 8787D)

FEATURES

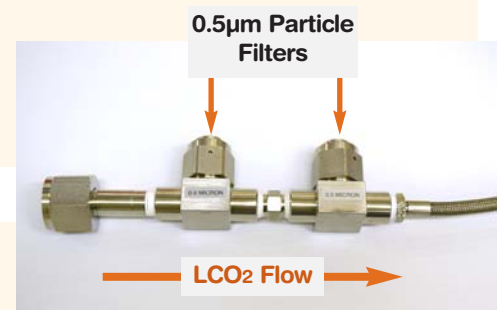
- Cleanroom Material Fabricated Static Free Design
- Bright LCD Touchscreen Control
- Default "Automode" setting suitable for most wafer and die MEMS applications
- Process up to 5 substrates per process run (either Wafers or Die)
- HF Compatible Holders for 10mm square die included with system
- Create and save custom Recipes exactly for your specific sample needs
- Easy View Placement of Micro Metering Valves with Vernier Handles
- Slow Fill feature protects the most delicate samples
- Fast adiabatic chamber cooling (\approx 1 minutes from 25°C to 3°C)
- Maintenance Free Non-Mechanical Vortex Swirl™ Purge Stirring
- External 0.5 μ m Post-Purge filter access for easy preventive maintenance
- External LCO₂ tank supply particulate filtration using 'Double T-Filter' design with 99.5%+ retention
- Internal filtration delivers filtered LCO₂ down to 0.08 μ m with 99.999+% retention directly into process chamber
- Internal SOTER™ Condenser quietly separates waste alcohol and CO₂ while eliminating any freeze up or static discharge
- EZ top loading process chamber with LED illumination
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SPECIFICATIONS

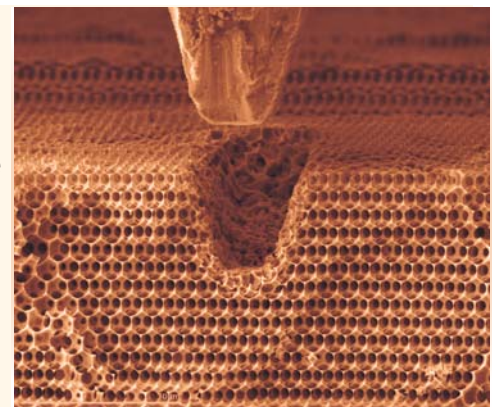
- Cabinet: (W) 15.0" (38.0cm) x (H) 13.25" (33.5cm) x (D) 20" (50.8cm)
- System Set-Up Area Required: (W) 24" (61cm) x (D) 22" (56cm)
- Chamber size:
 1.25" ID x 1.25" Depth (31.75mm ID x 31.75mm Depth) - 25ml Volume
- Pressure Gauge Range: 0 to 2000 psi, Temperature Range - 30°C to 60°C
- 120V or 220V Models Available



Double T-Filter Assembly (#8785)
 Pre-Installed onto High Pressure Hose

STANDARD ACCESSORIES

- Flexible High-Pressure LCO₂ Supply Hose, 10ft (3.0m)
 Note: Other lengths available upon request up to 50ft (15m)
- HF Compatible Substrate Holder included: 10mm square die holder for up to 5 die
- Double T-Filter Assembly (#8785-see insert picture) pre-installed onto the LCO₂ high-pressure hose. LCO₂ filtered twice thru 0.5 μ m filters prior to LCO₂ entering Autosamdri®-931 process chamber
- Static Free Exhaust Tubing
- Flow Meter supplied allows precise BLEED Exhaust Calibration
- Spare chamber O-rings (2), LED chamber lamp (1), and 5A slo-blow fuses (2)
- User Manual and Check-Out Data Sheet
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